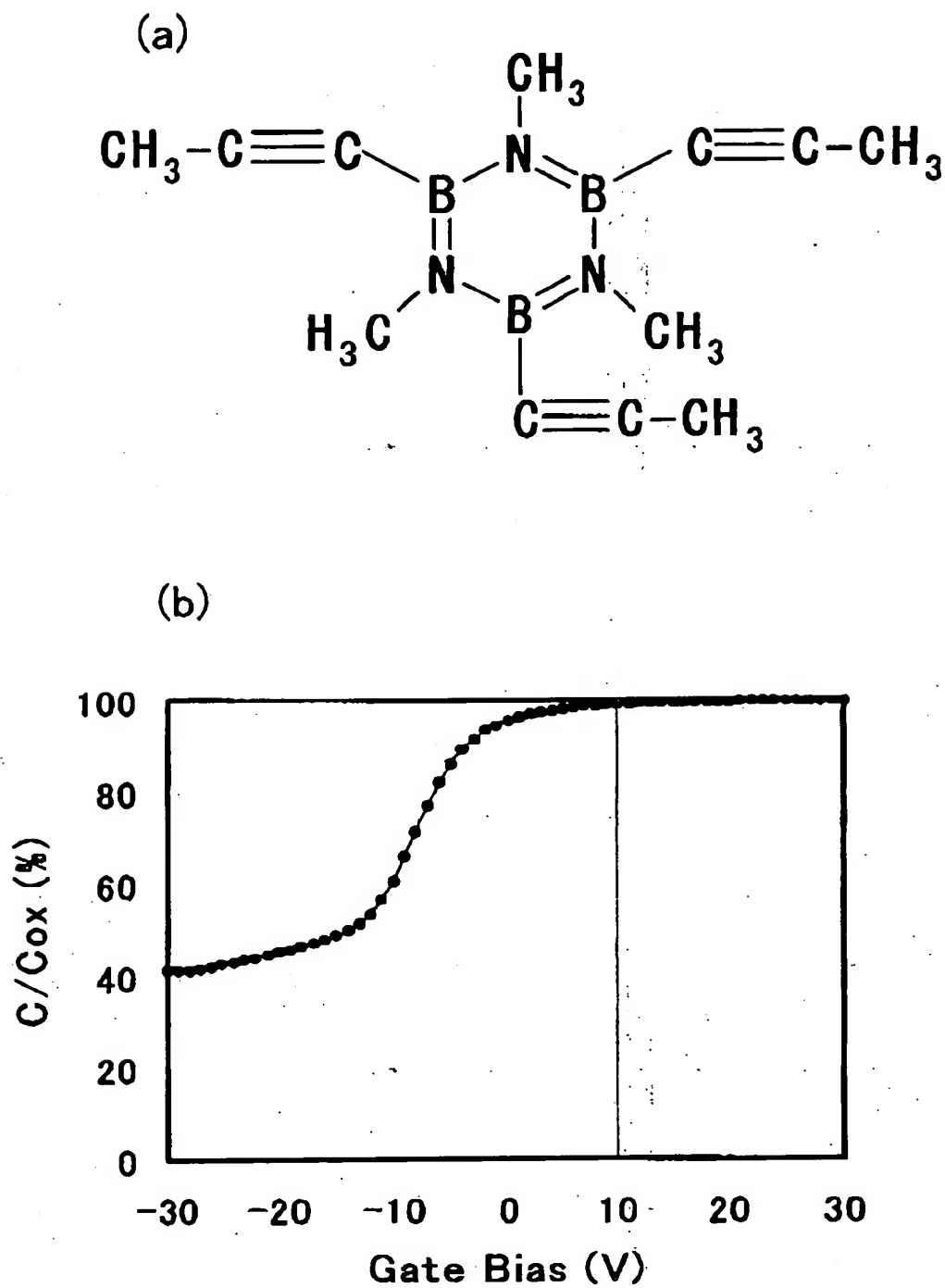


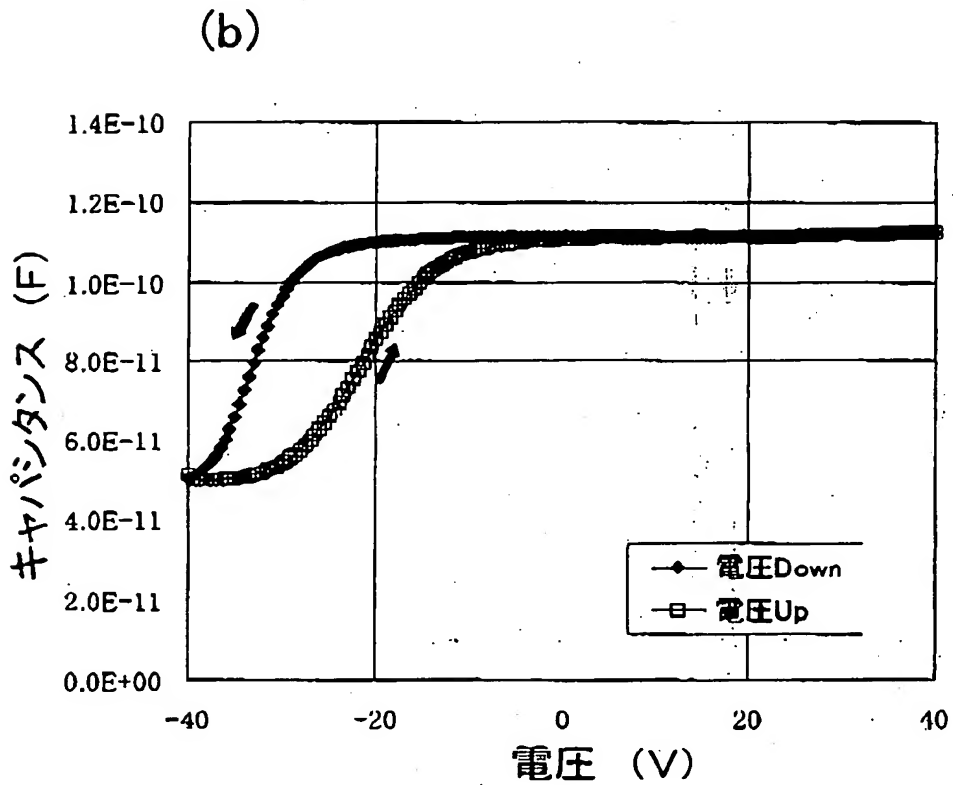
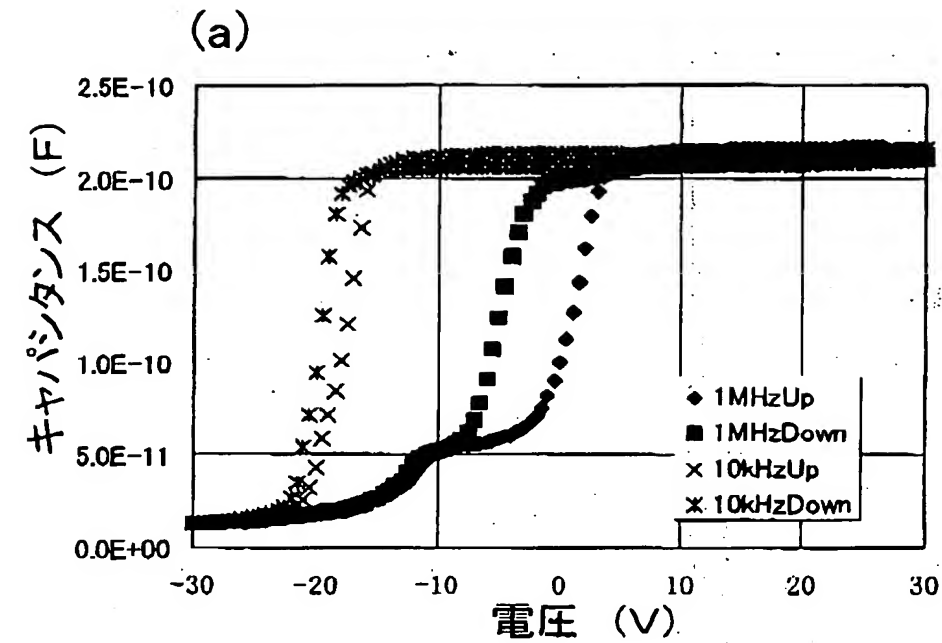
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FIG. 1



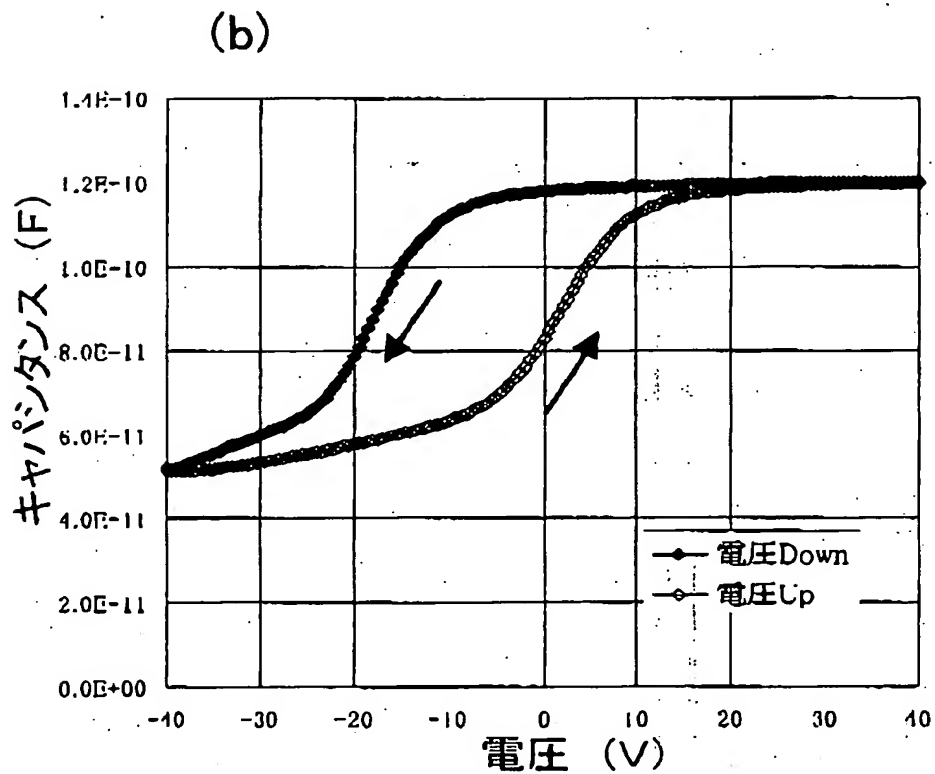
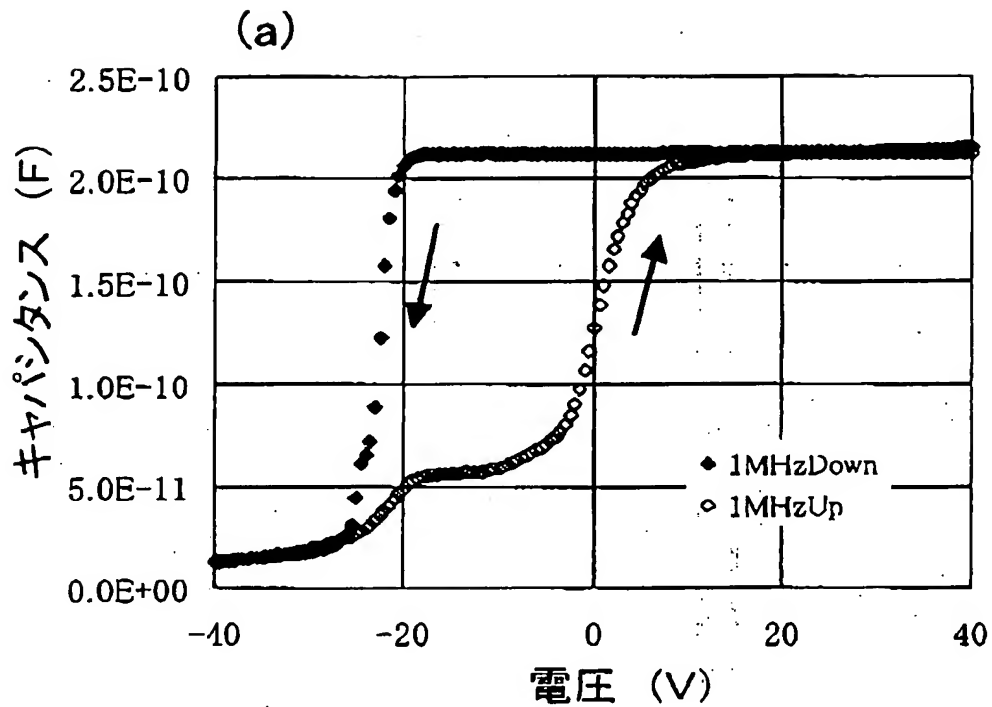
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FIG. 2



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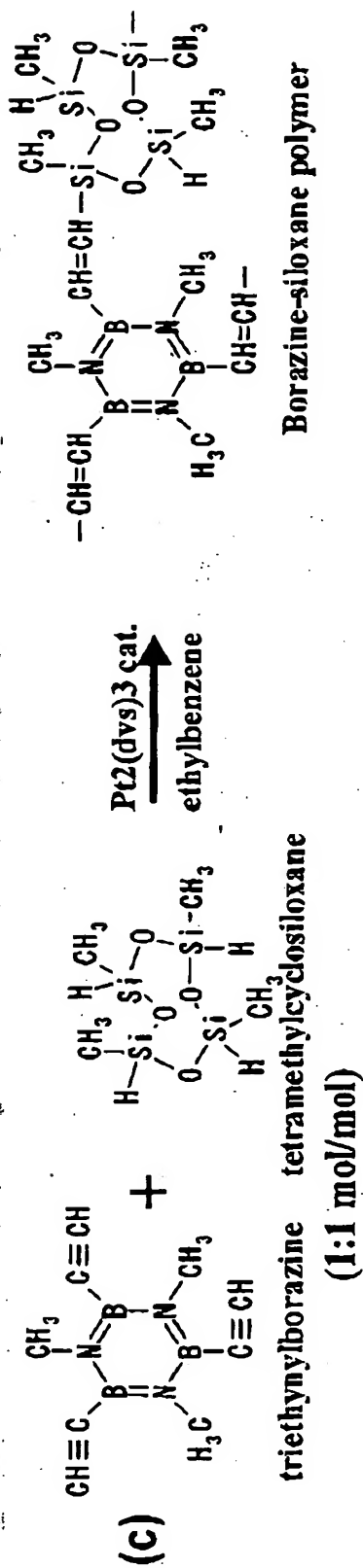
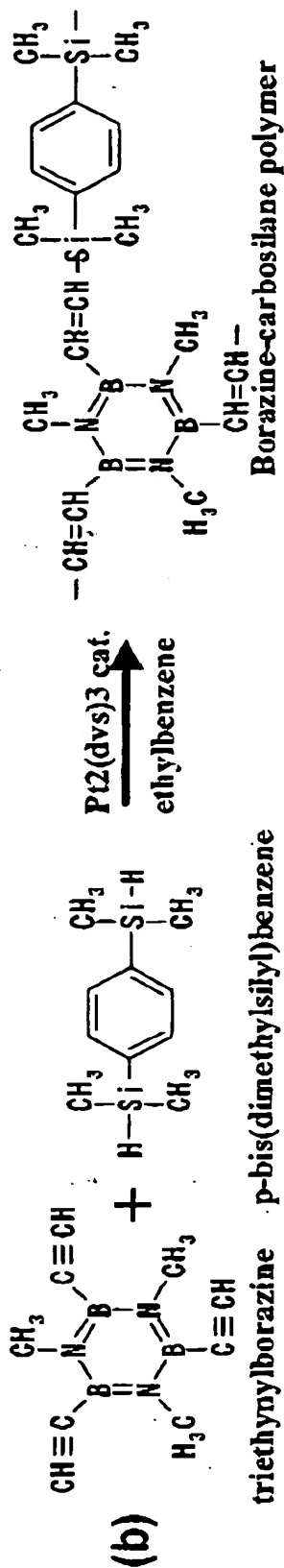
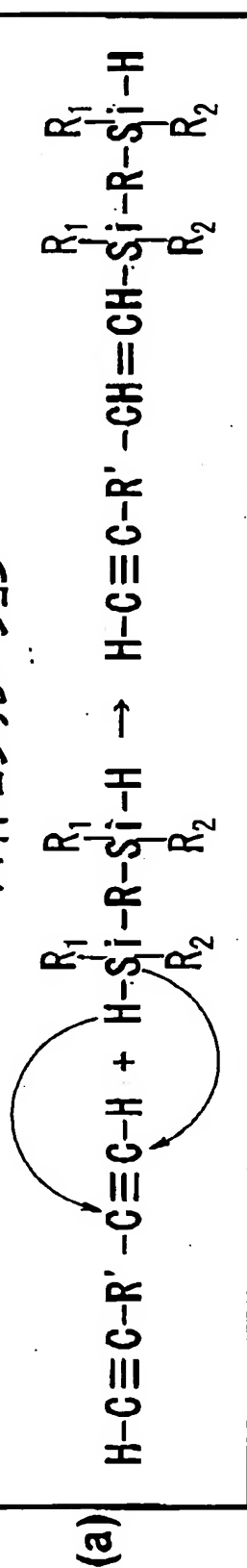
FIG. 3



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FIG. 4

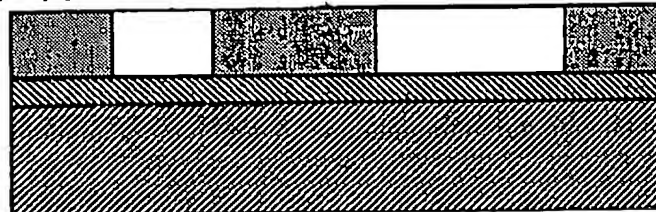
ハイドロシリレーション



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FIG. 5

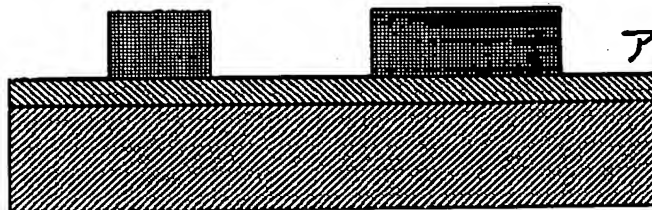
試料にメタルマスクを取り付け



メタルマスク
ポリイミドポリマー
シリコン基板

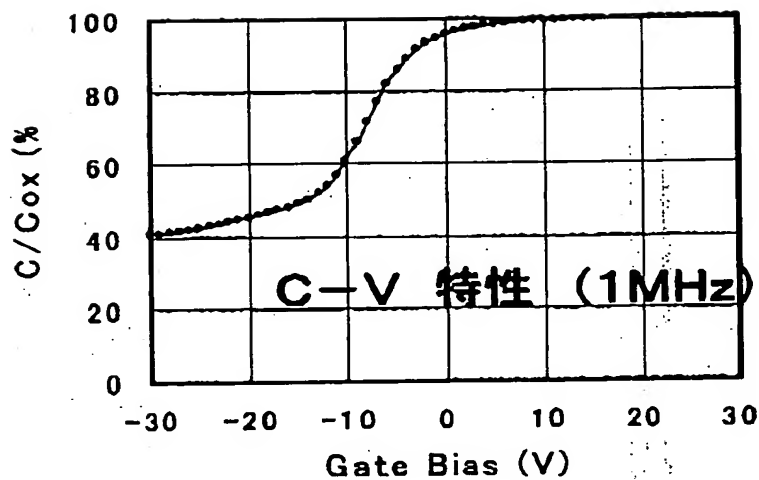
(a)

アルミニウム蒸着後メタルマスクを除去



アルミニウム電極

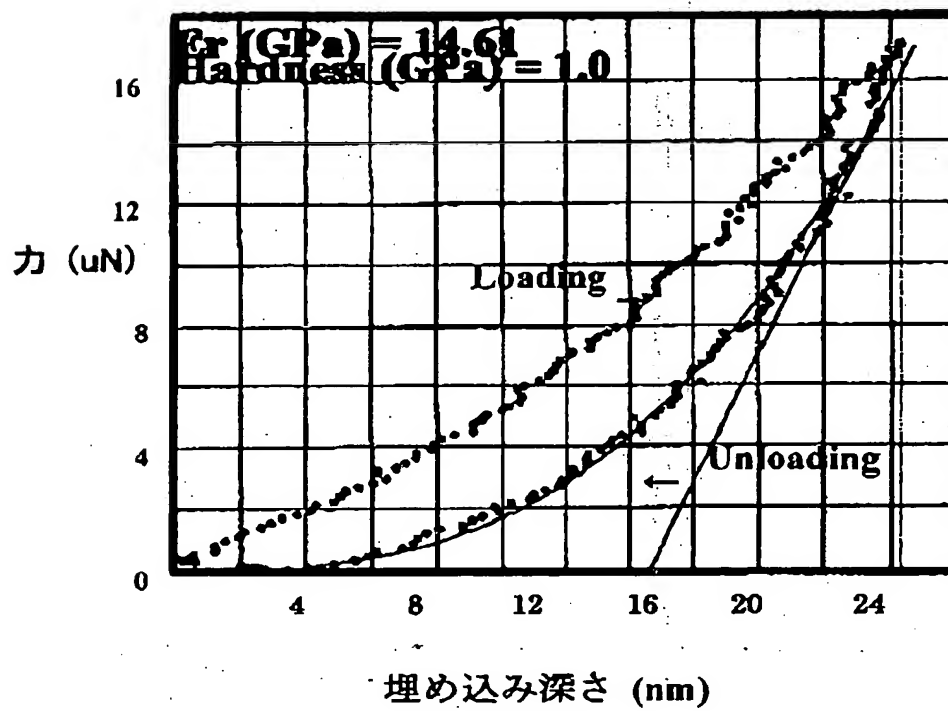
(b)



(c)

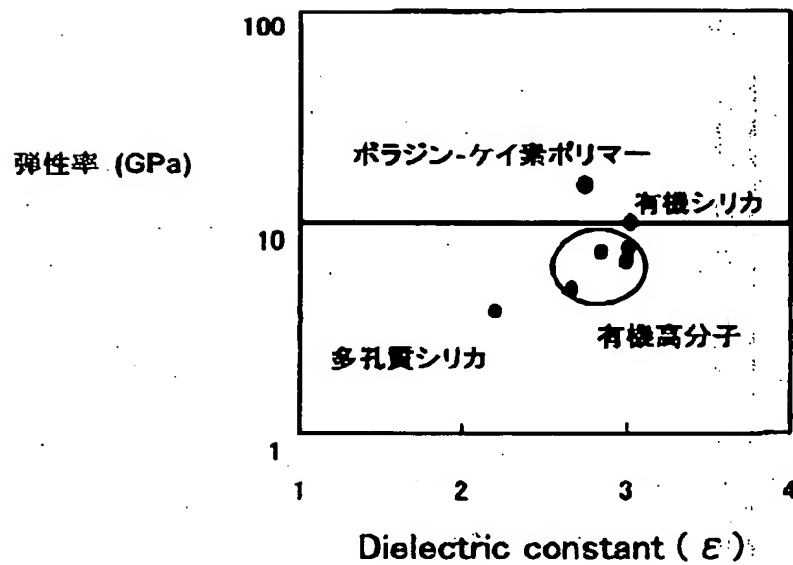
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FIG. 6

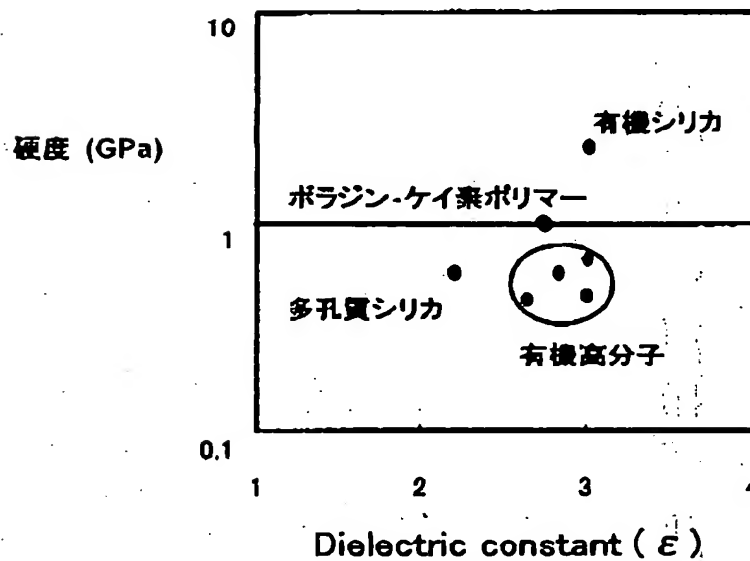


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FIG. 7



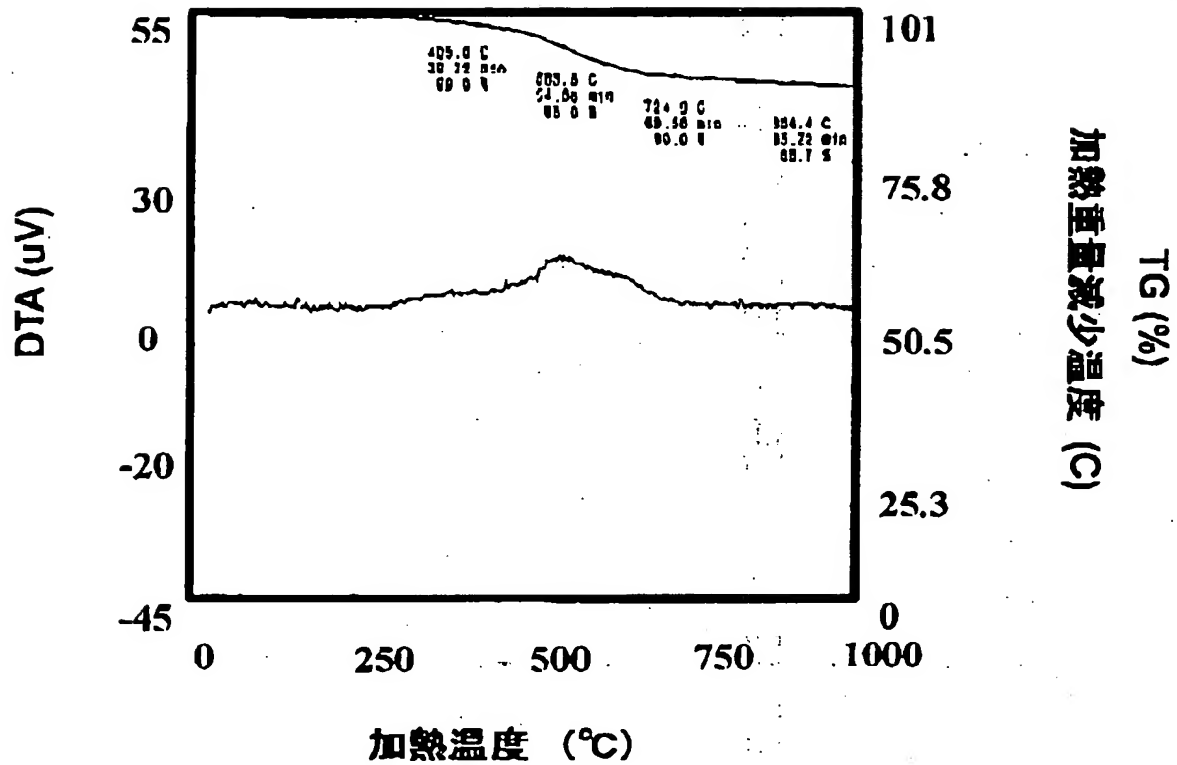
(a) 弾性率



(b) 硬度

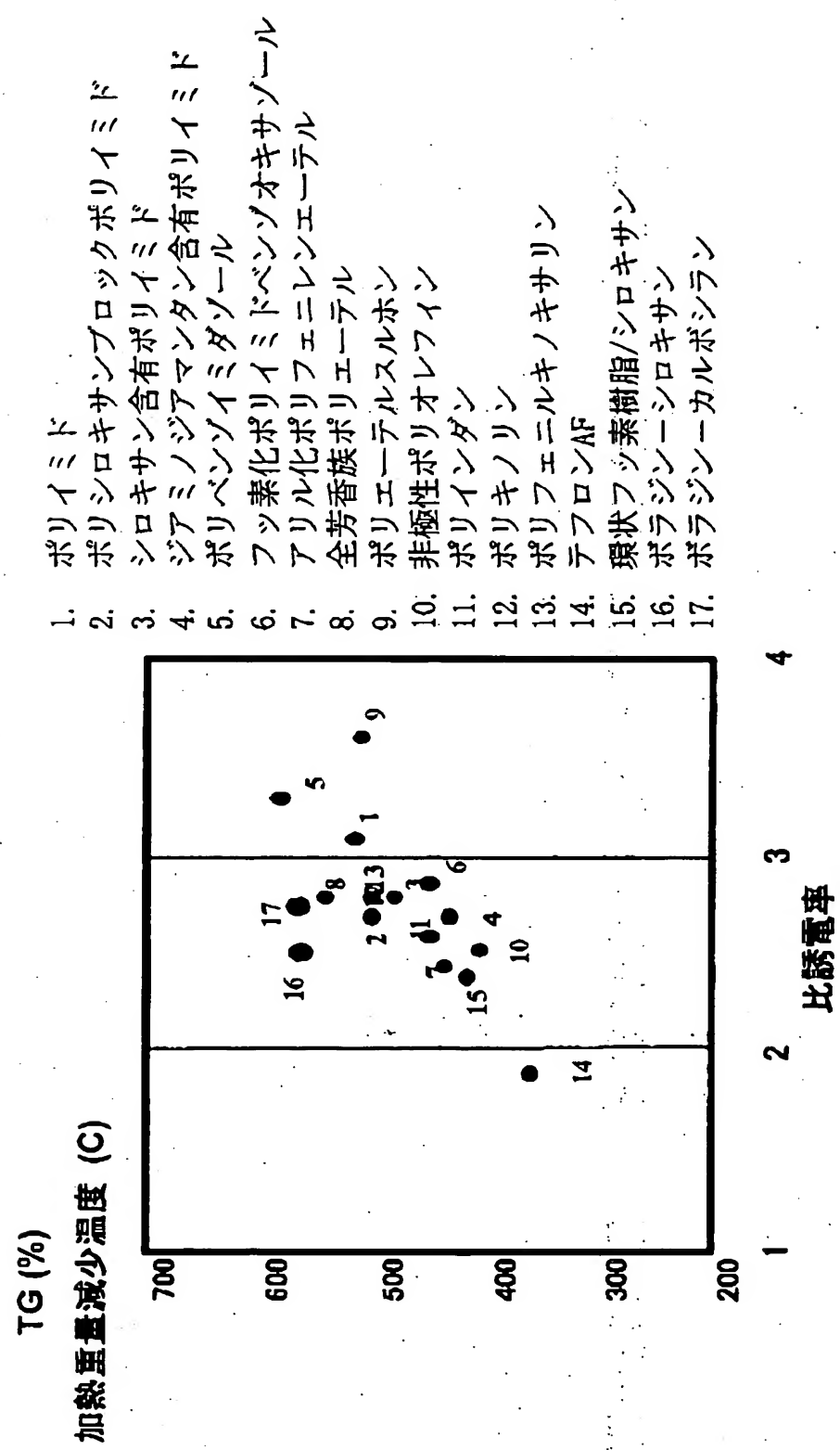
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FIG. 8



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FIG. 9



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FIG. 10

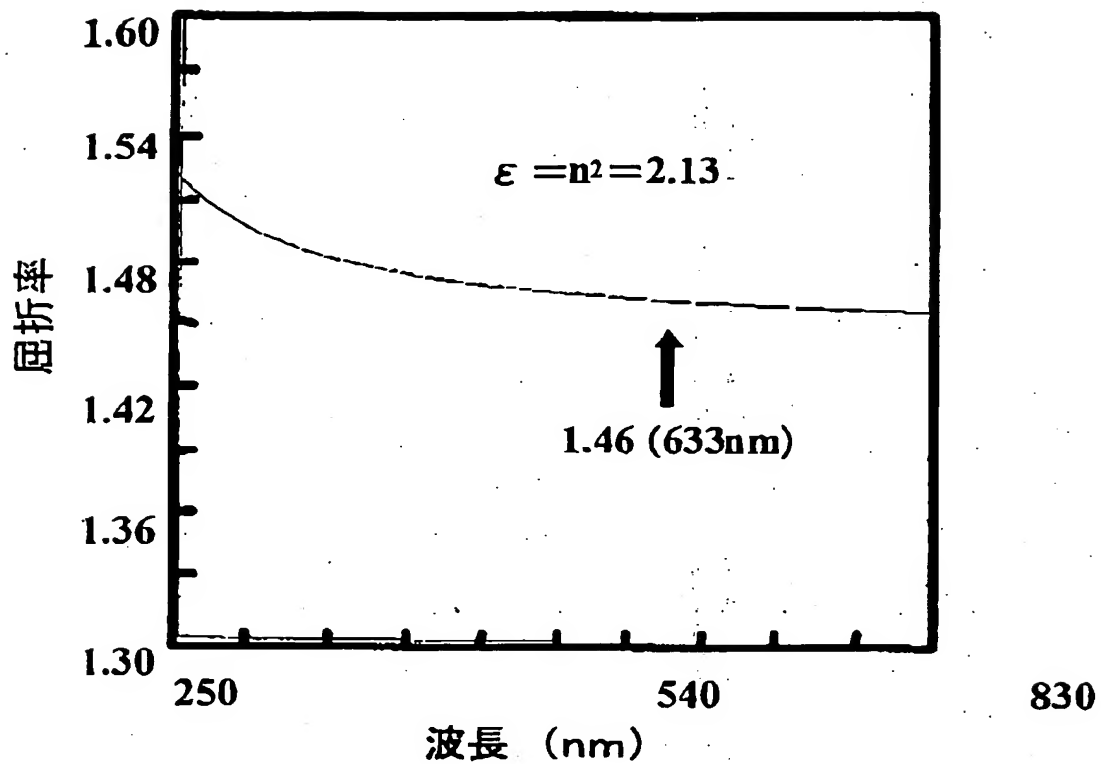
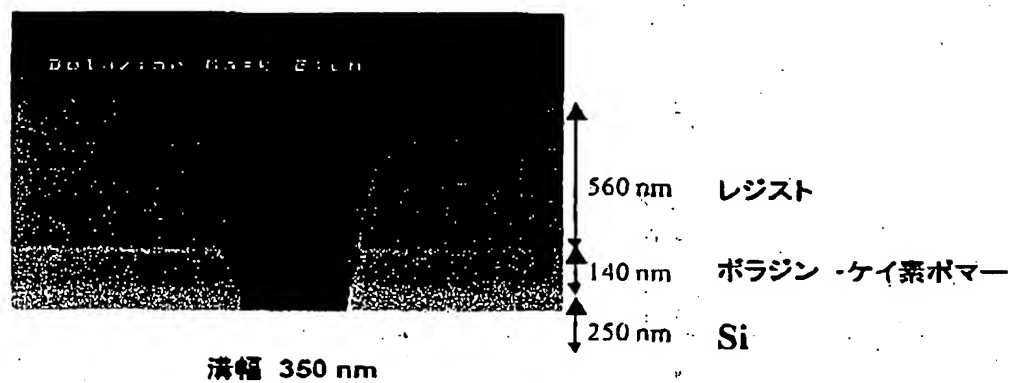
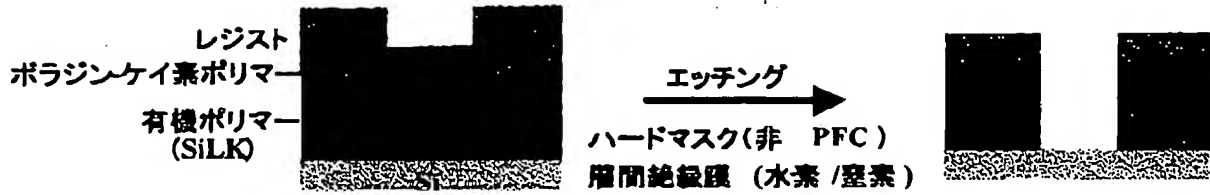


FIG. 11



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FIG. 12

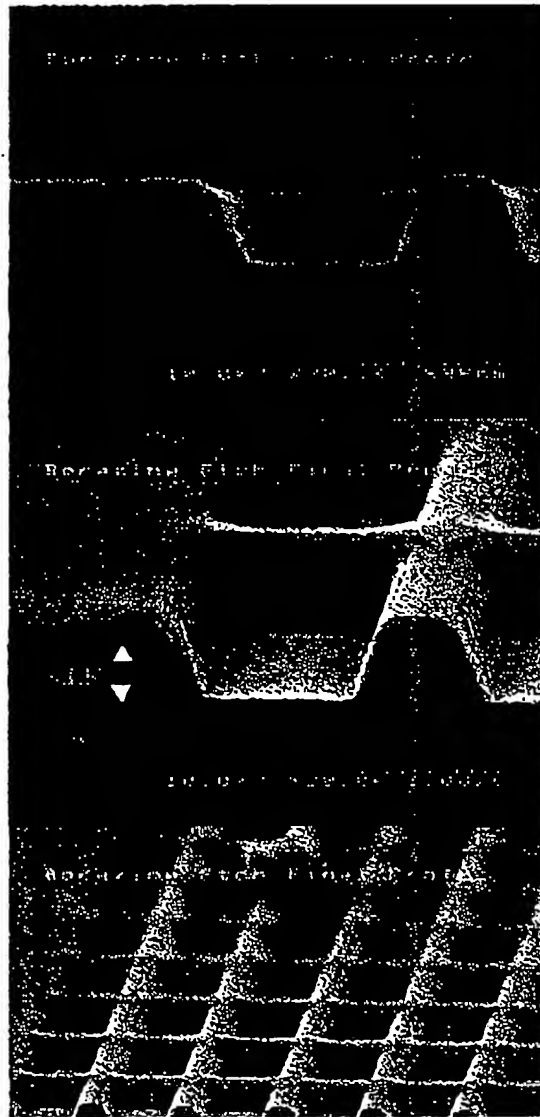


(a)

(b)

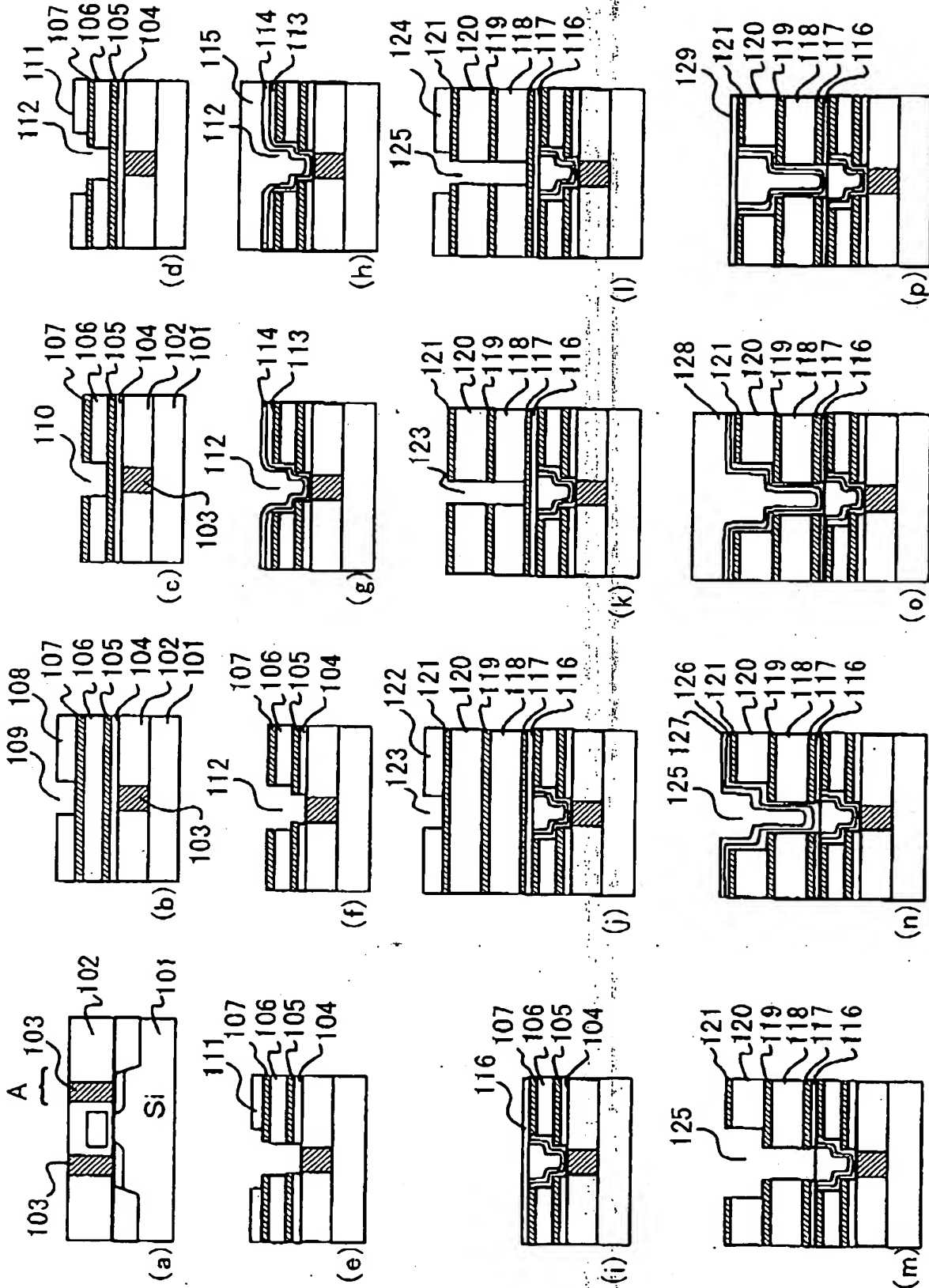
(c)

(d)



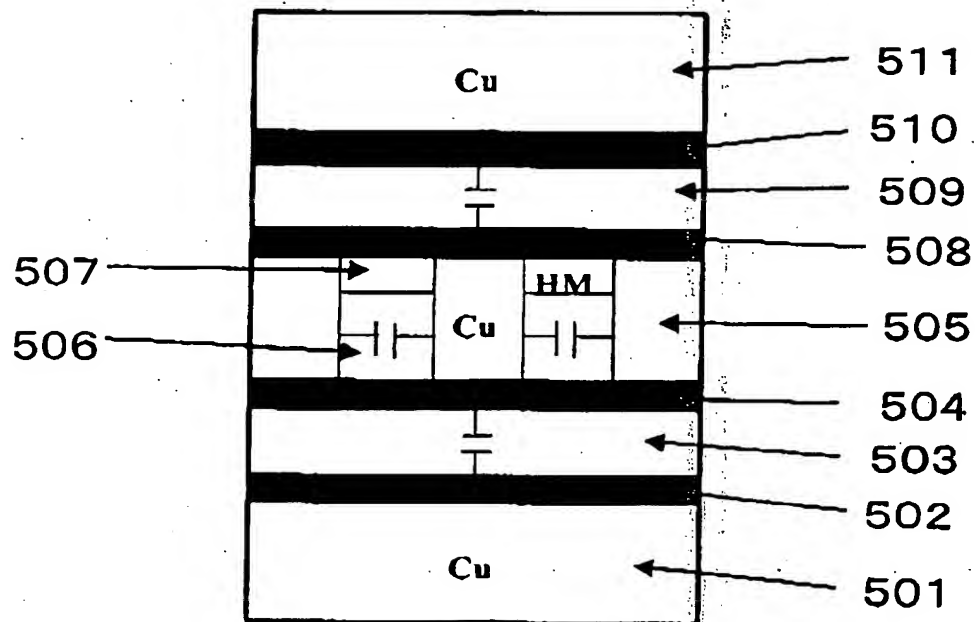
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FIG. 13



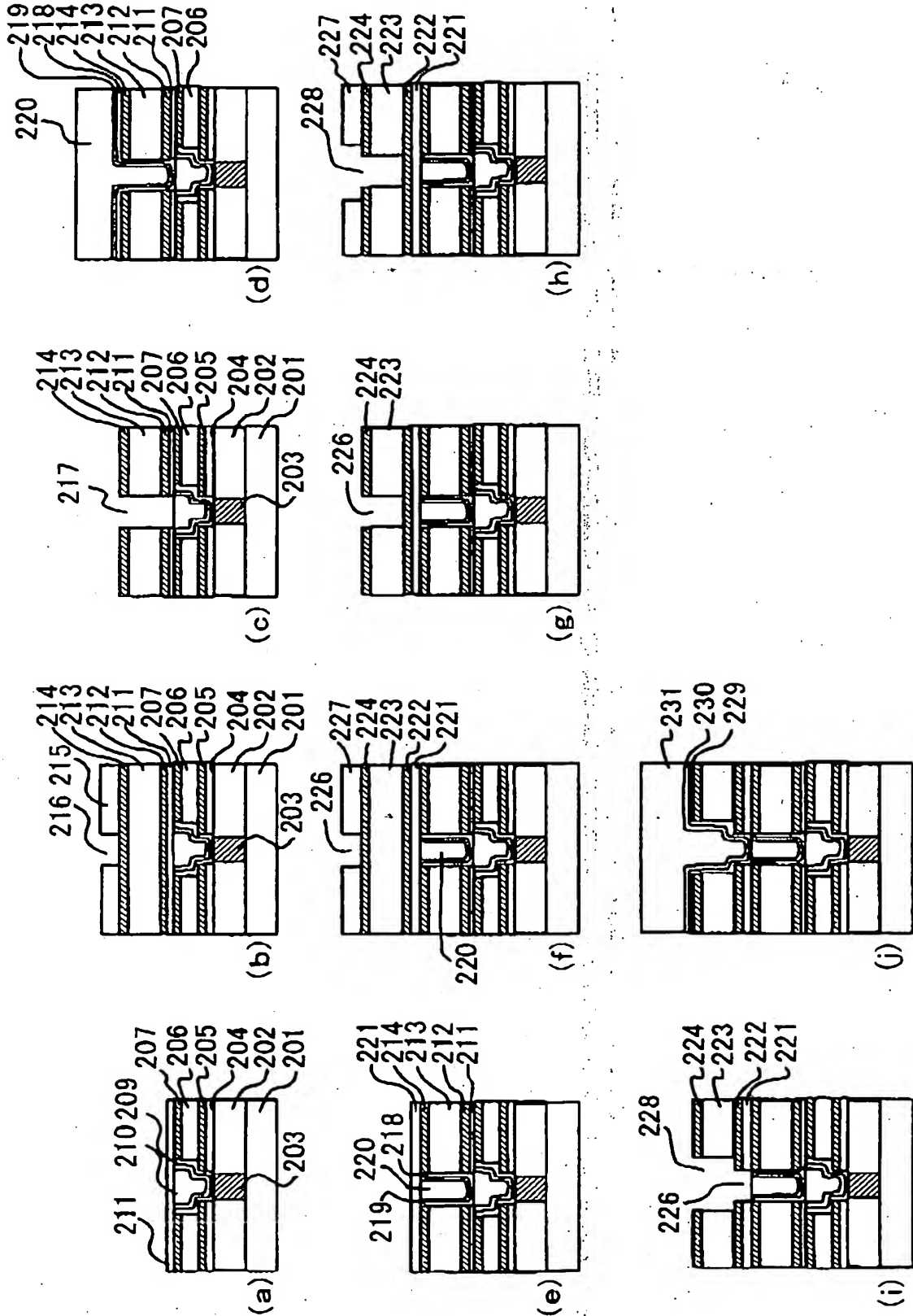
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FIG. 14



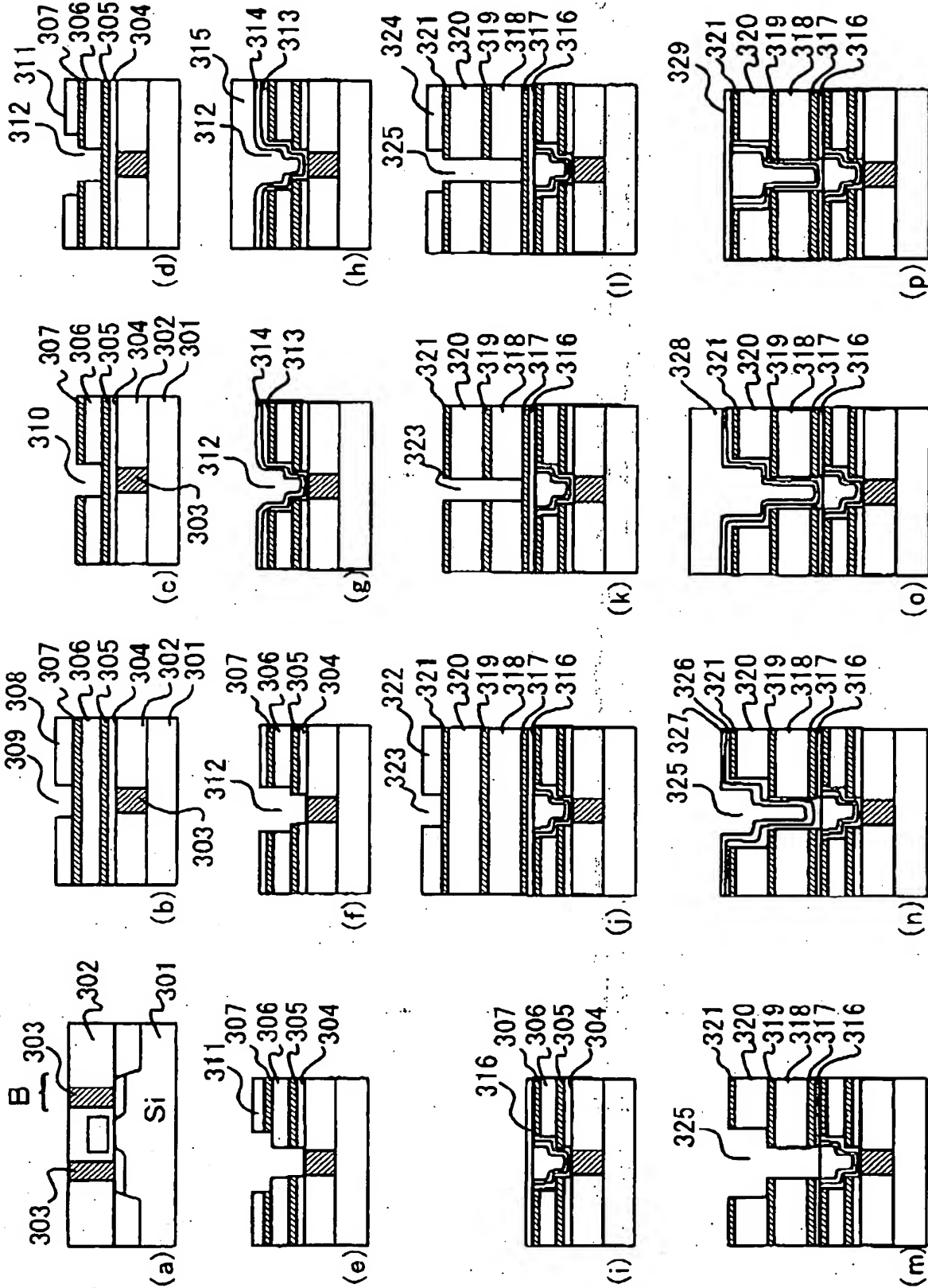
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FIG. 15



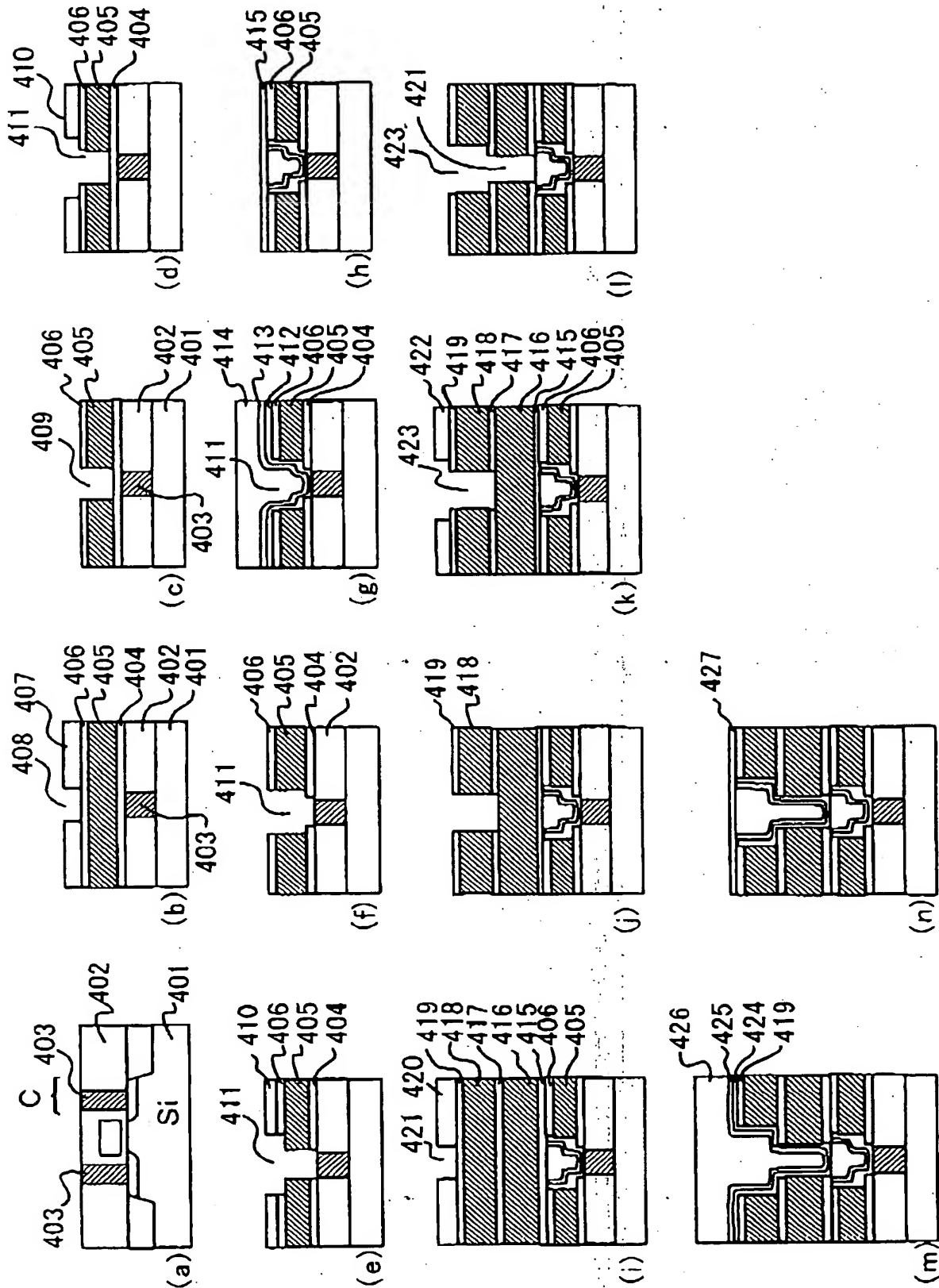
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FIG. 16



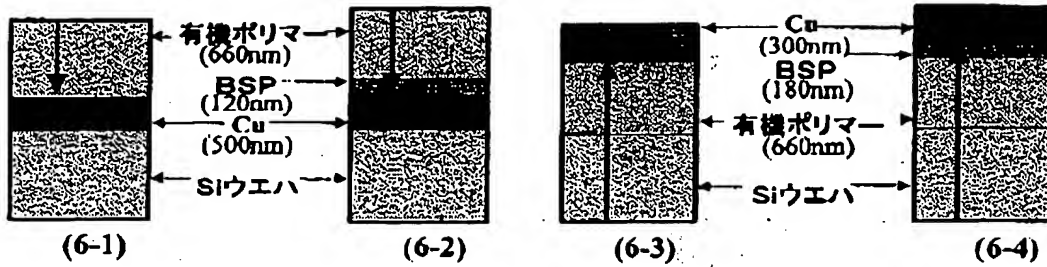
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FIG. 17



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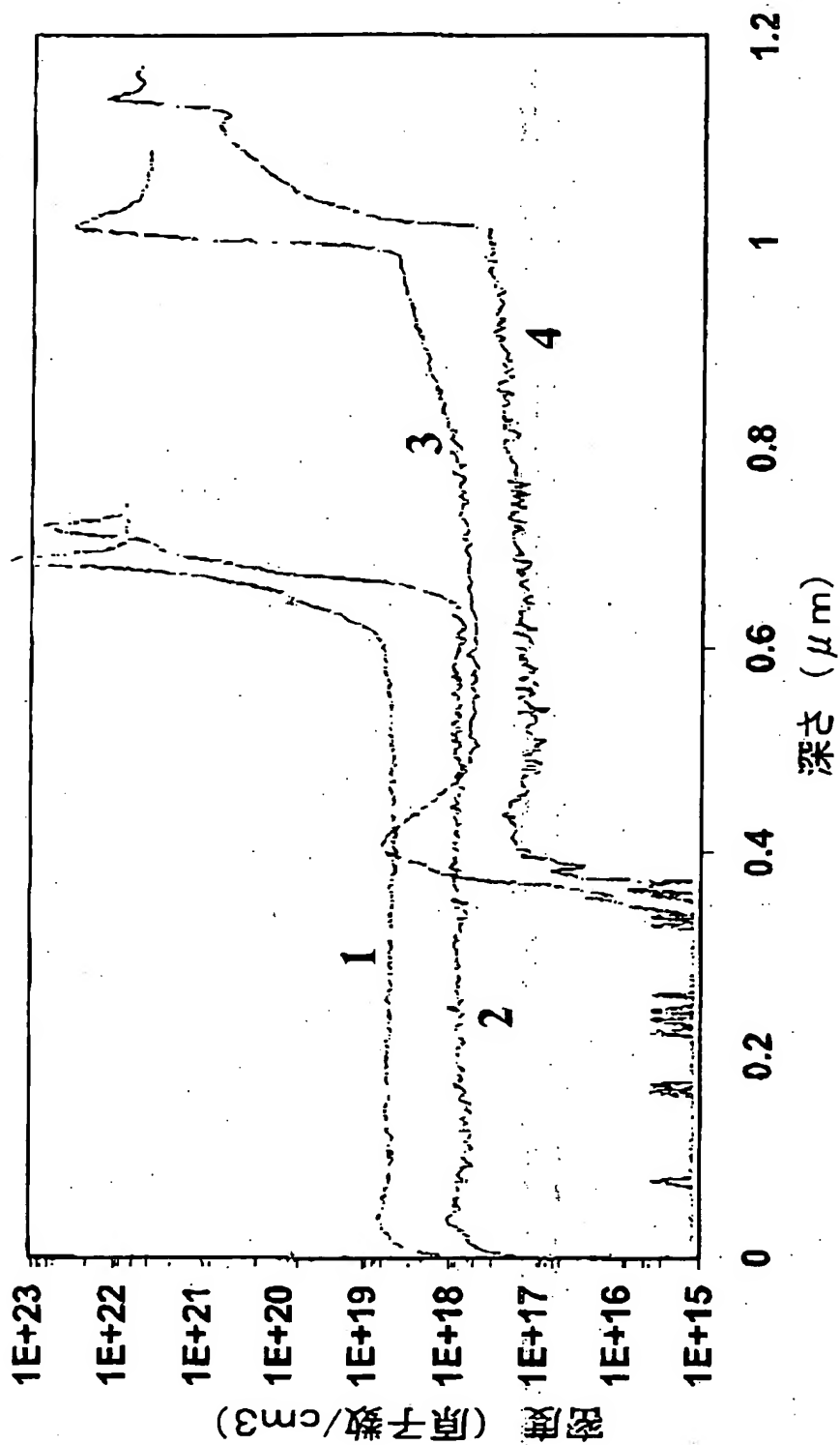
FIG. 18



	構造	Cu atoms/cm ³
1	Si / Cu(500nm) / OP(660nm)	5×10^{18}
2	Si / Cu(500nm) / BSP(120nm) / OP(660nm)	8×10^{17}
3	Si / OP(660nm) / Cu(300nm)	6×10^{17}
4	Si / OP(660nm) / BSP(180nm) / Cu(300nm)	1×10^{17}

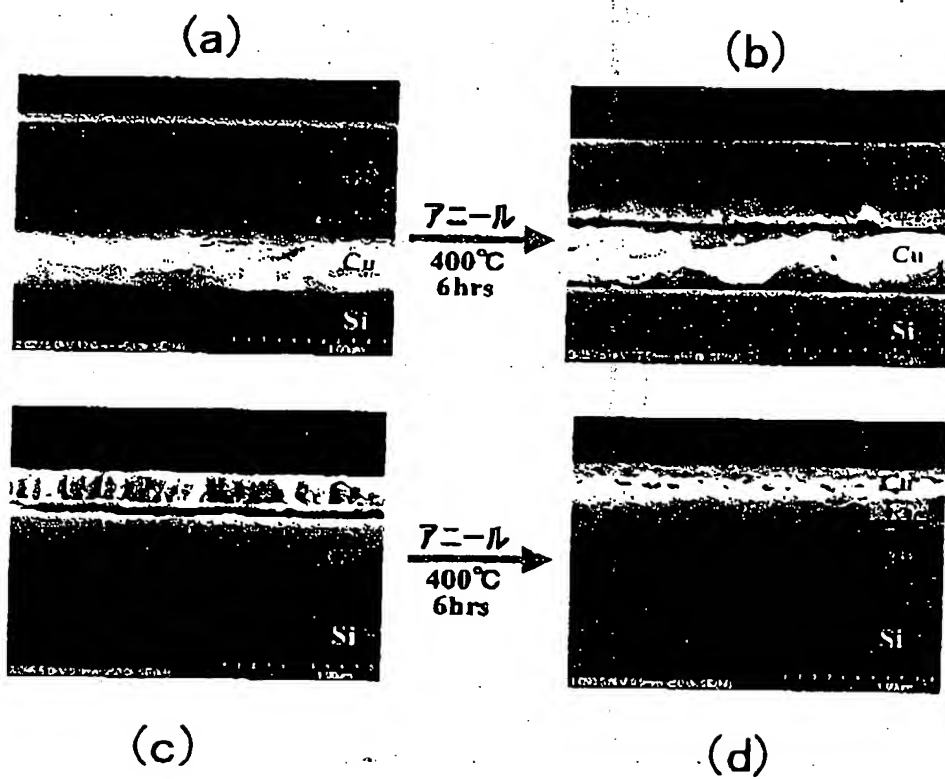
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FIG. 19



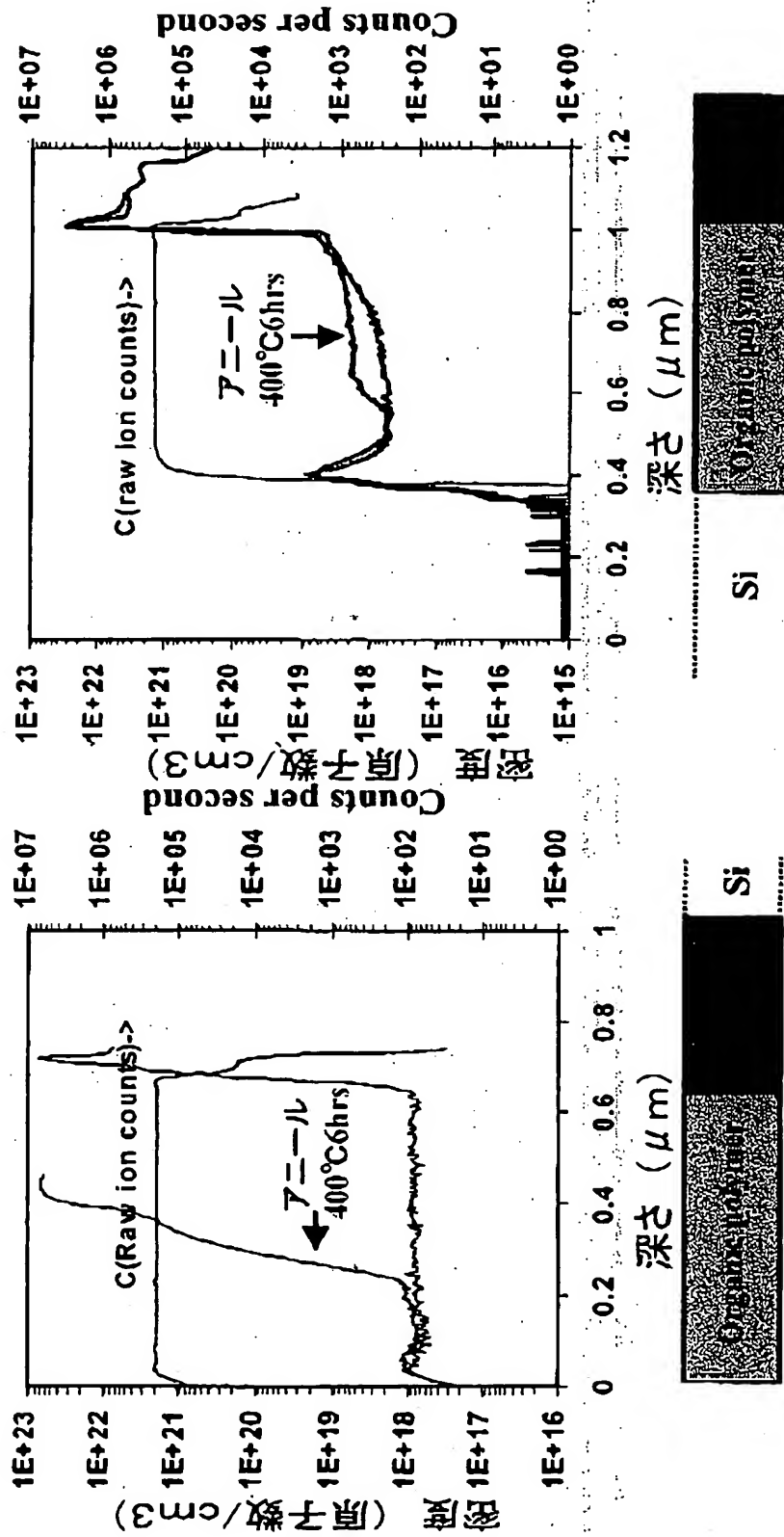
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FIG. 20



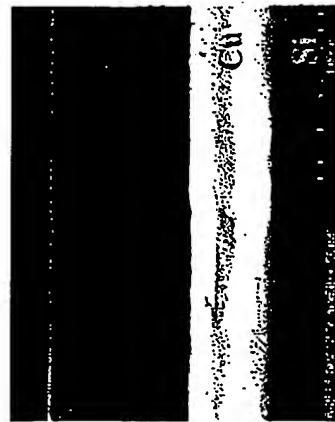
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FIG. 21



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FIG. 22

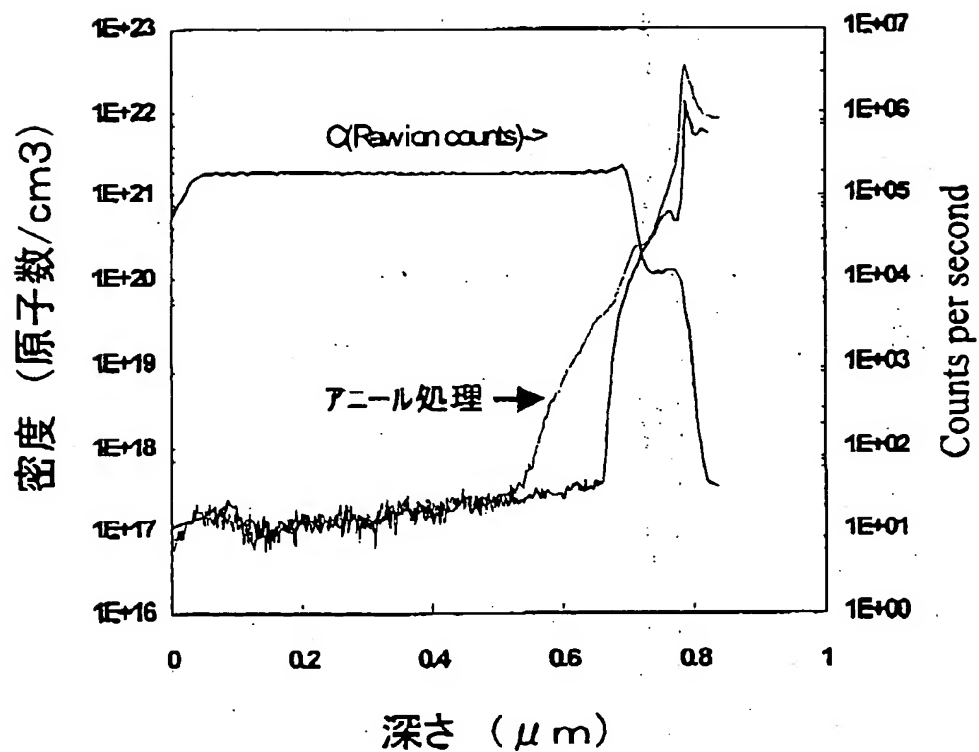


$\lambda = 2 \mu\text{m}$
↑
400°C · 6hrs



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FIG. 23



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FIG. 24

